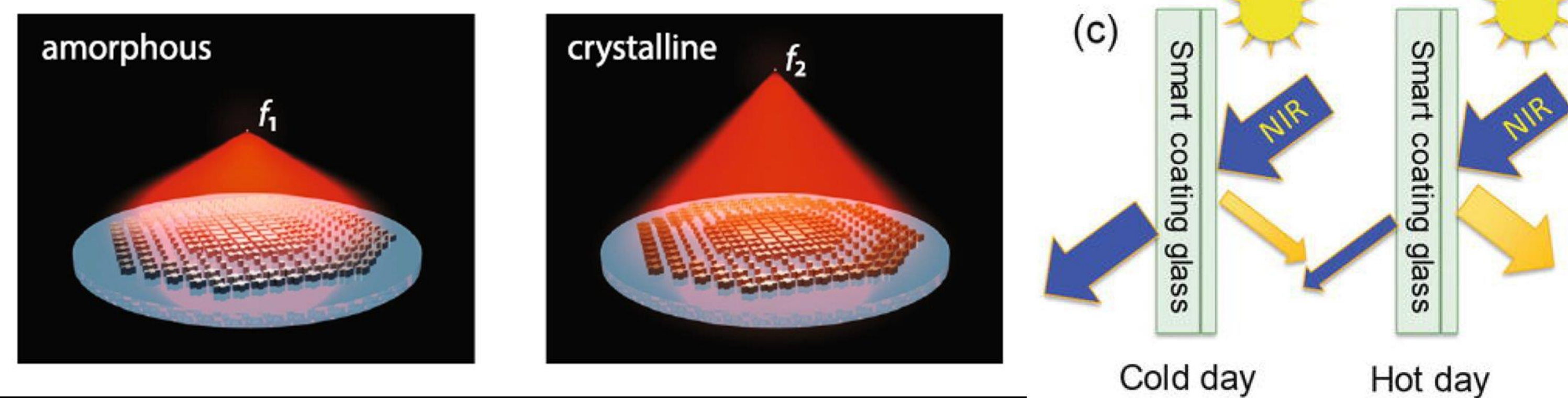


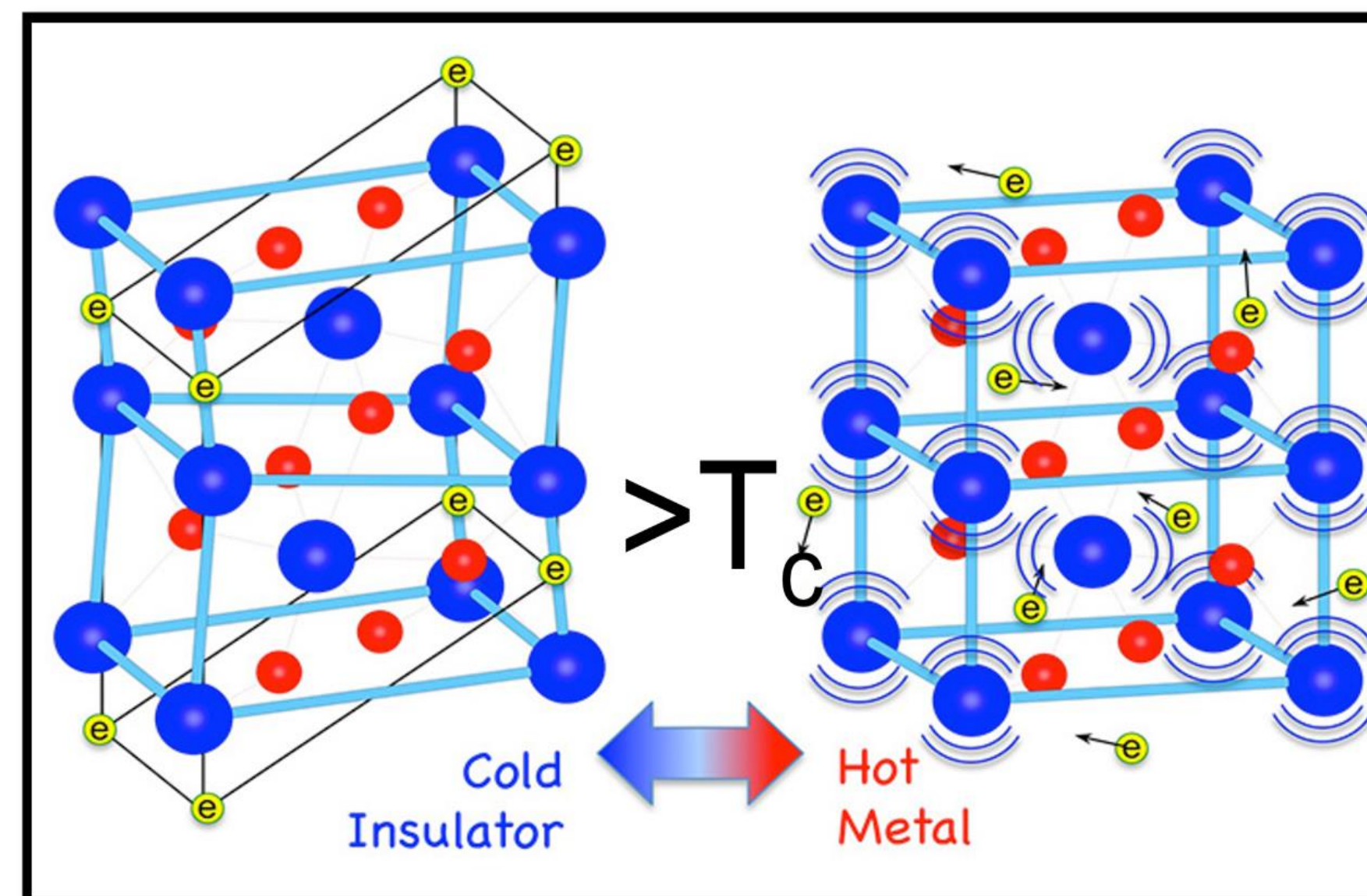
### Introduction

Vanadium dioxide thin films are useful for the creation of tunable photonic devices, smart windows and other opto-thermal devices



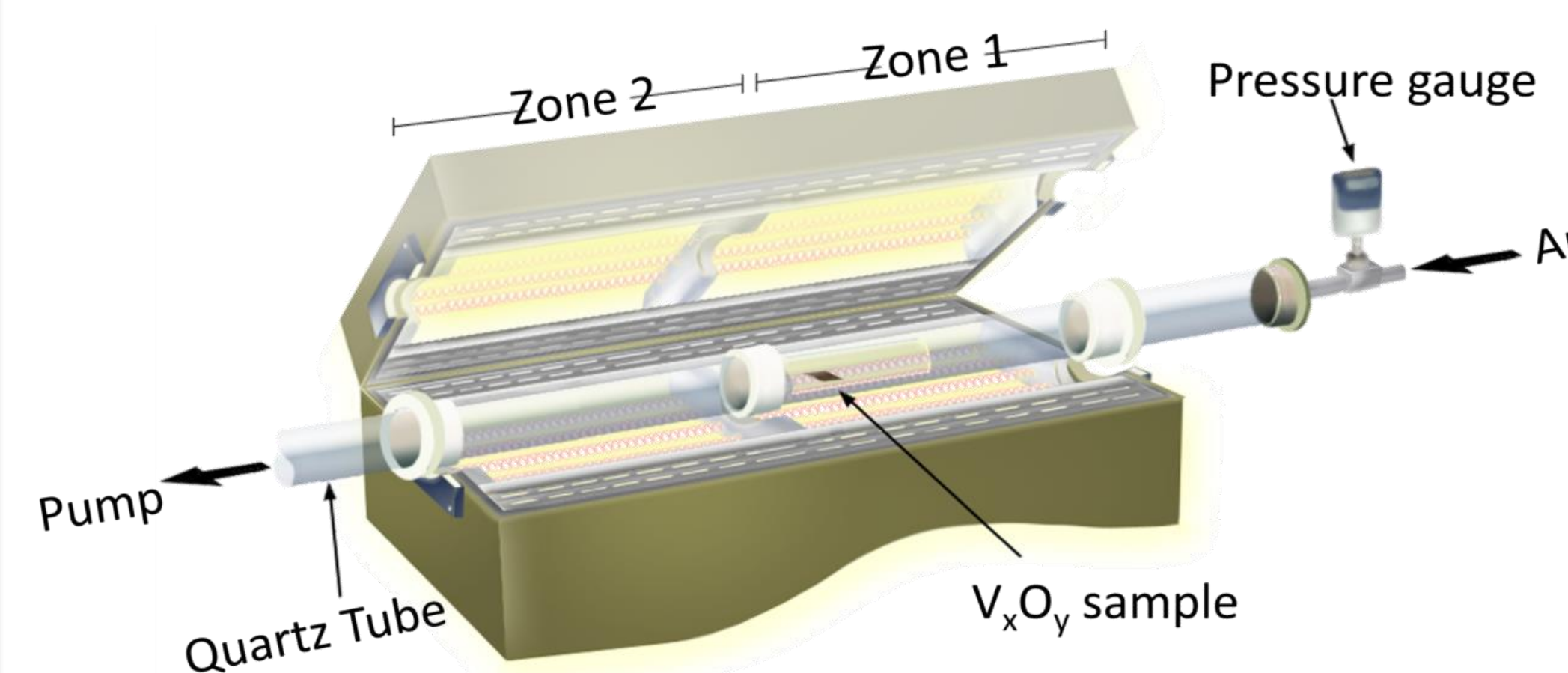
### VO<sub>2</sub> Background

- Vanadium dioxide is a phase transition material
- VO<sub>2</sub> has a reversible transition between phases around 68°C
- At lower temperatures, it acts as an insulator while at higher temperatures, it behaves as a metal



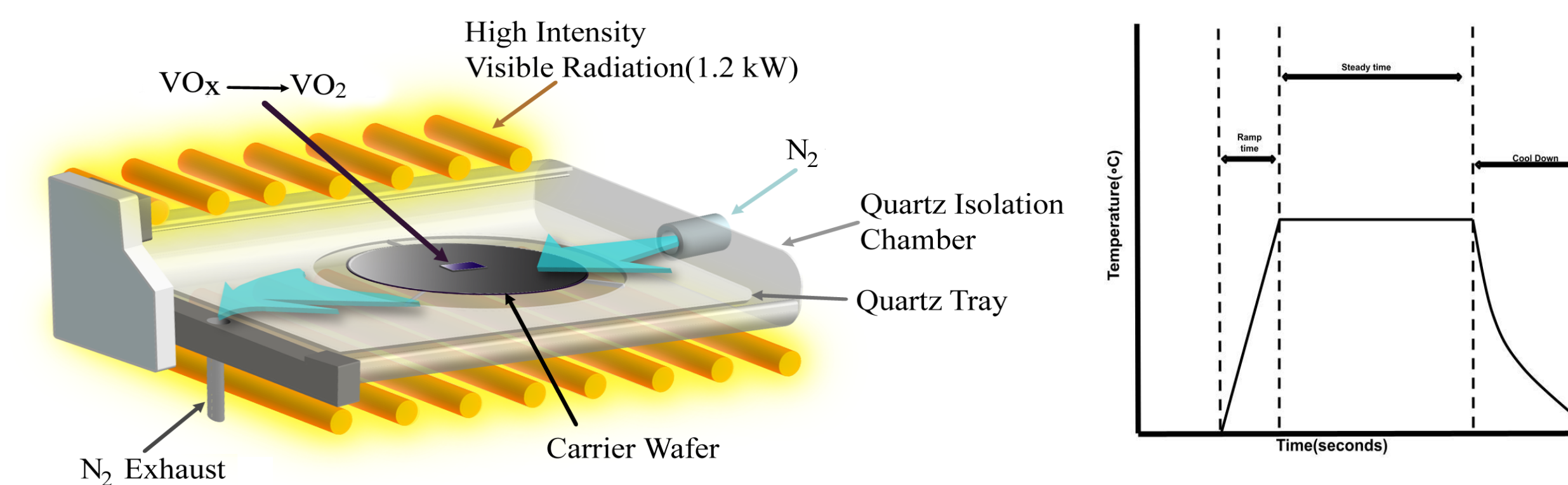
### Film Deposition

- VO<sub>x</sub> films are deposited in a two-step process:
  - Sputtering – Deposits a mixture of oxides
  - Tube Annealing – Reduces VO<sub>x</sub> to VO<sub>2</sub>



### Rapid Thermal Annealer

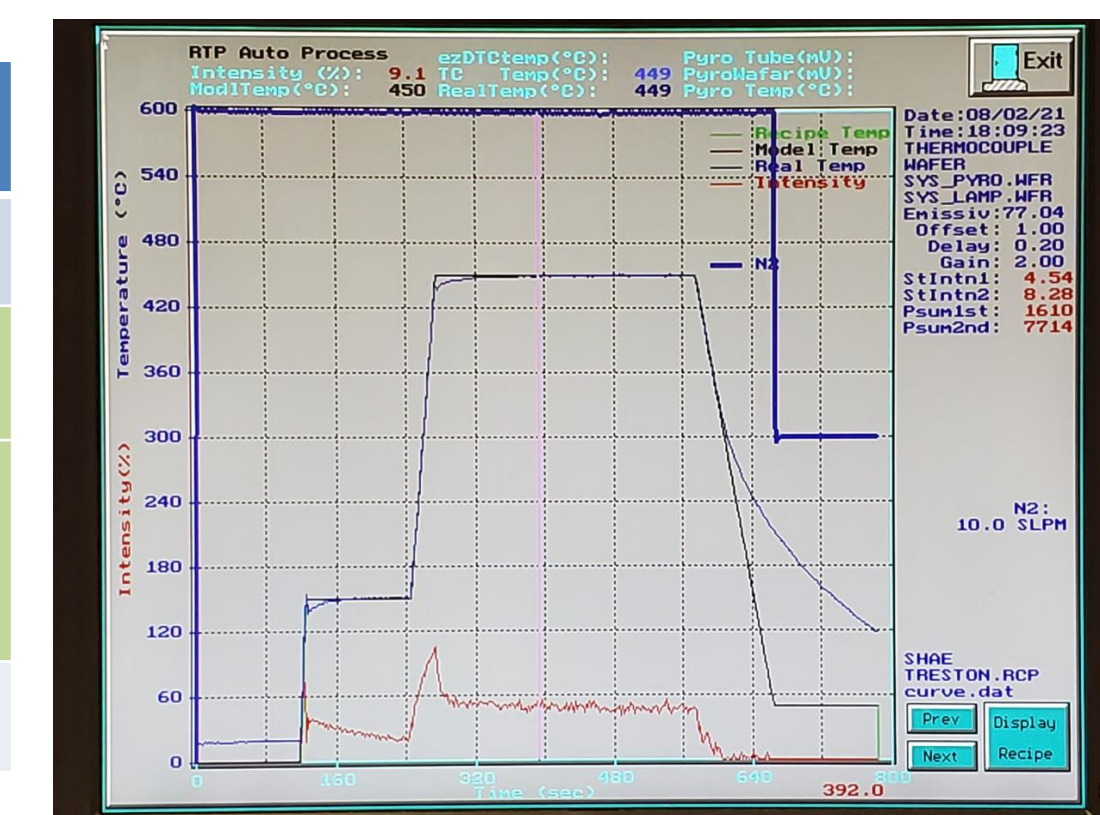
- Faster and more precise than tube annealing
- Uses high intensity visible radiation to heat single wafers for short process periods of time at precisely controlled temperatures.
- Atmosphere is saturated with N<sub>2</sub> to reduce Oxygen content.



### Annealing Parameters

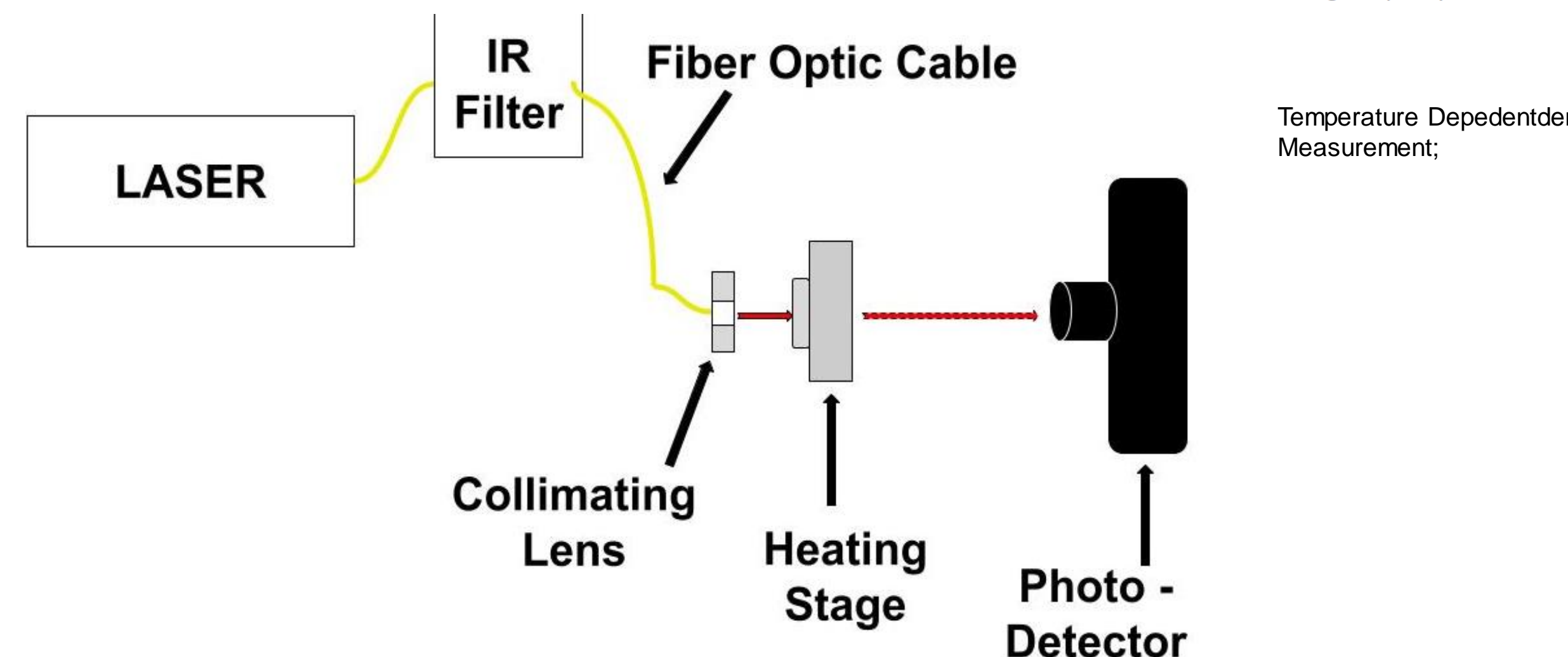
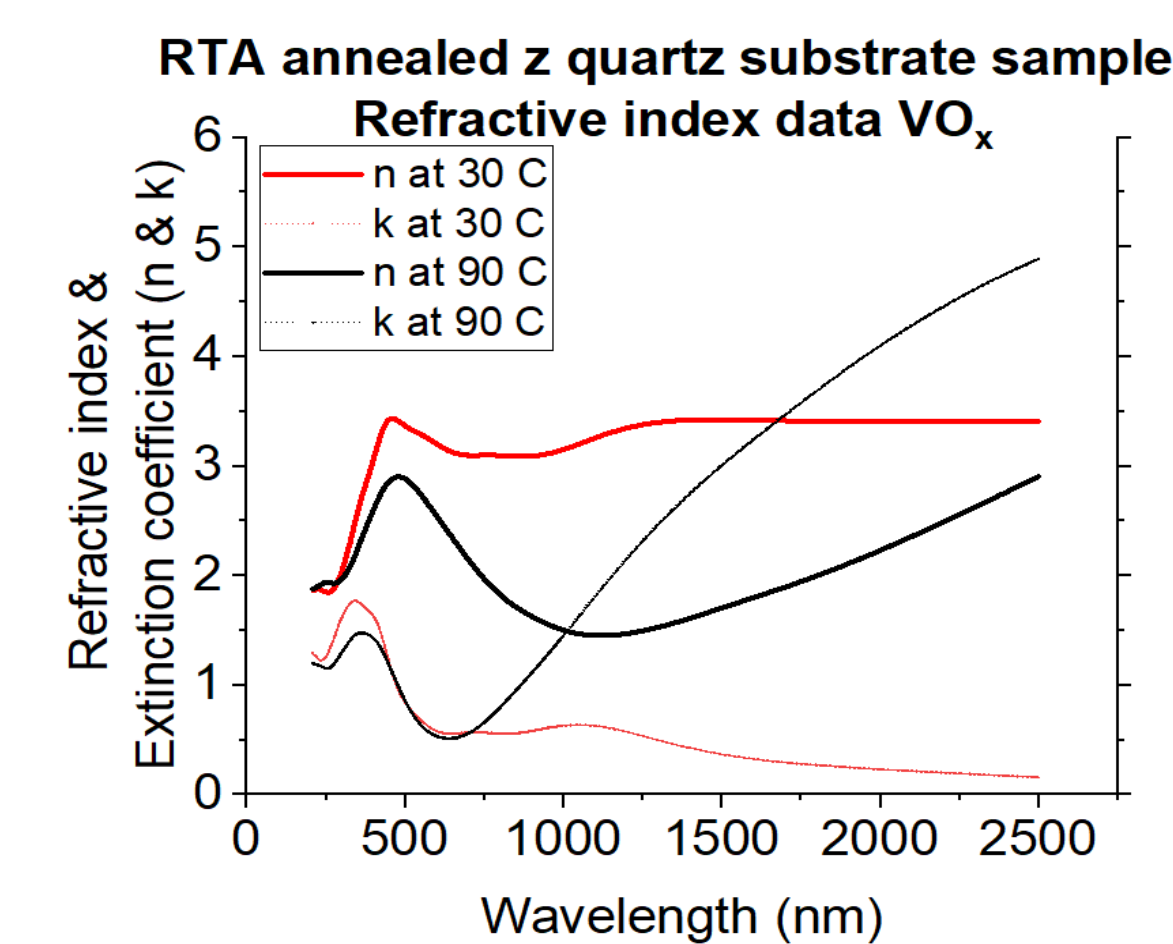
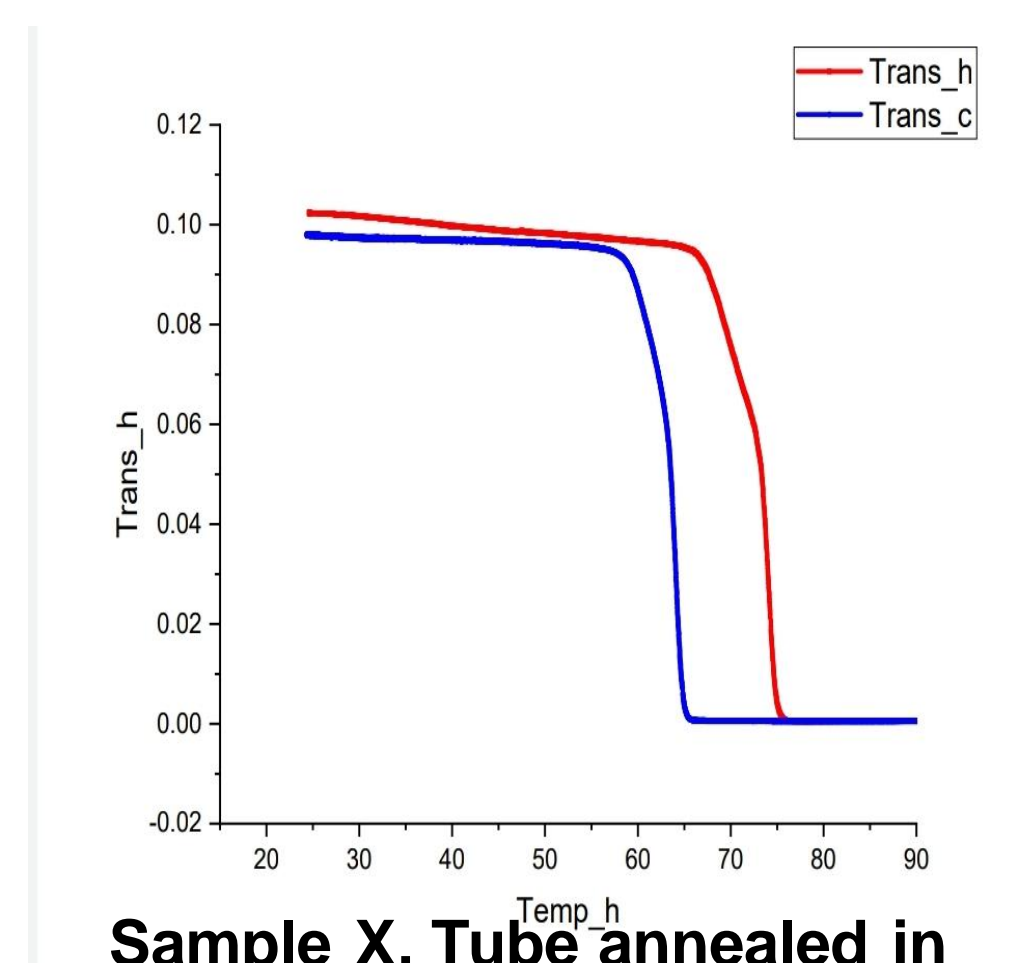
RTA process optimization was done by varying the following parameters:

Parameter	Value
Process gas	N <sub>2</sub>
Steady Time	60-1200s
Temperature	450-500, primary; 300-600, total
Flow rate	10 slpm

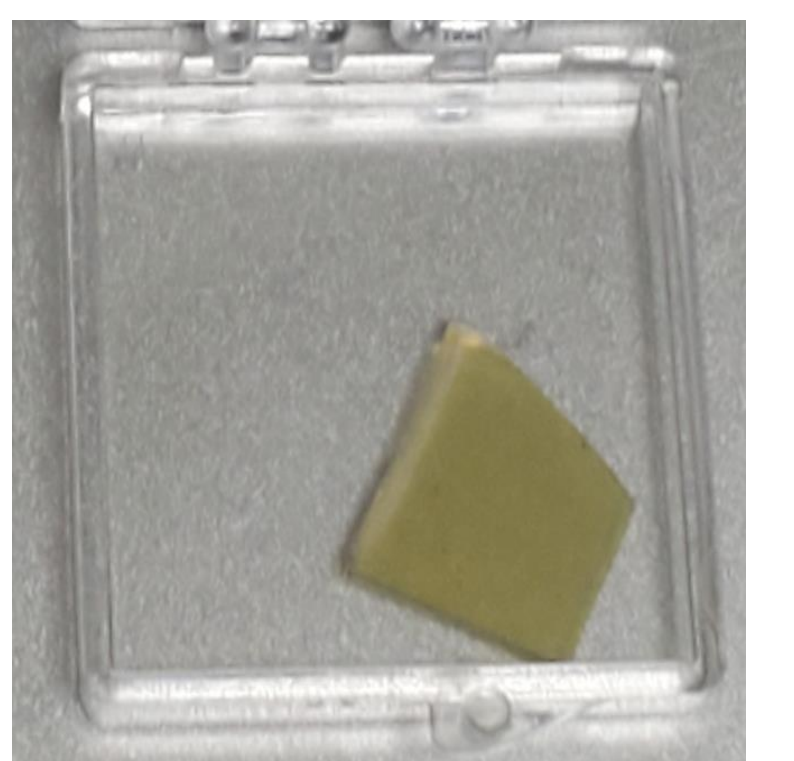
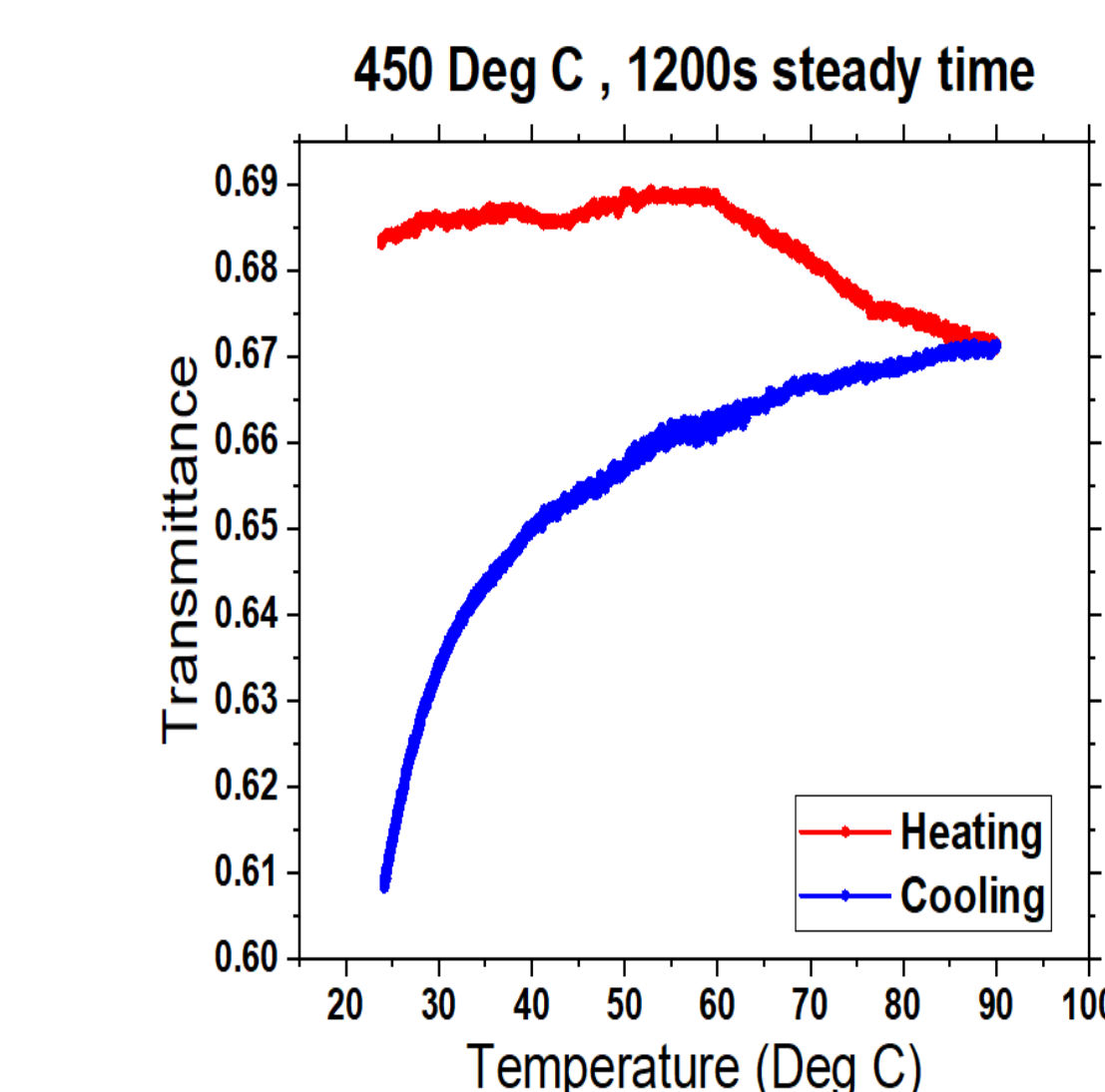
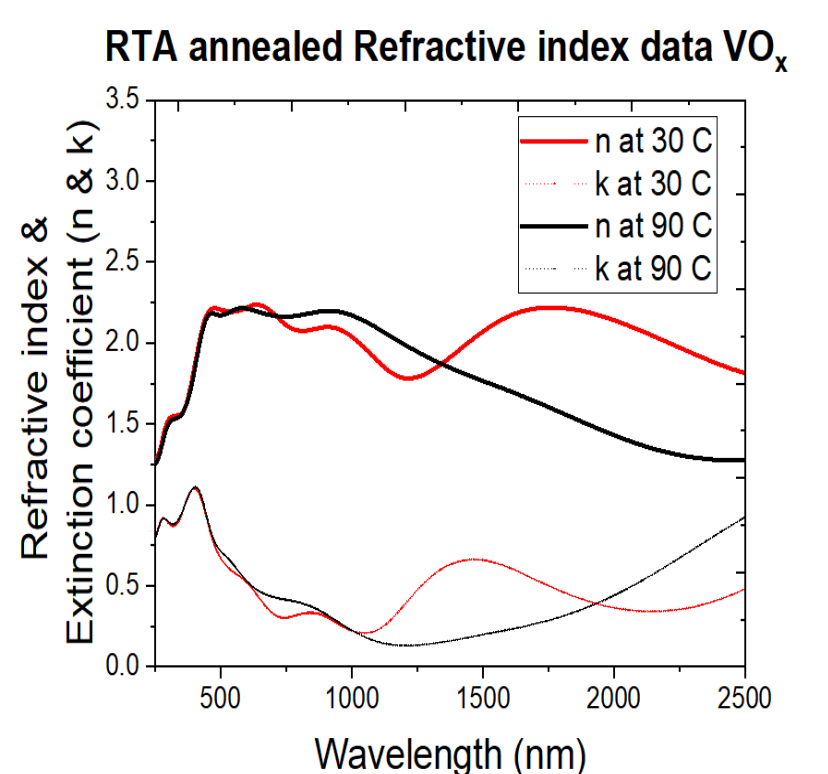
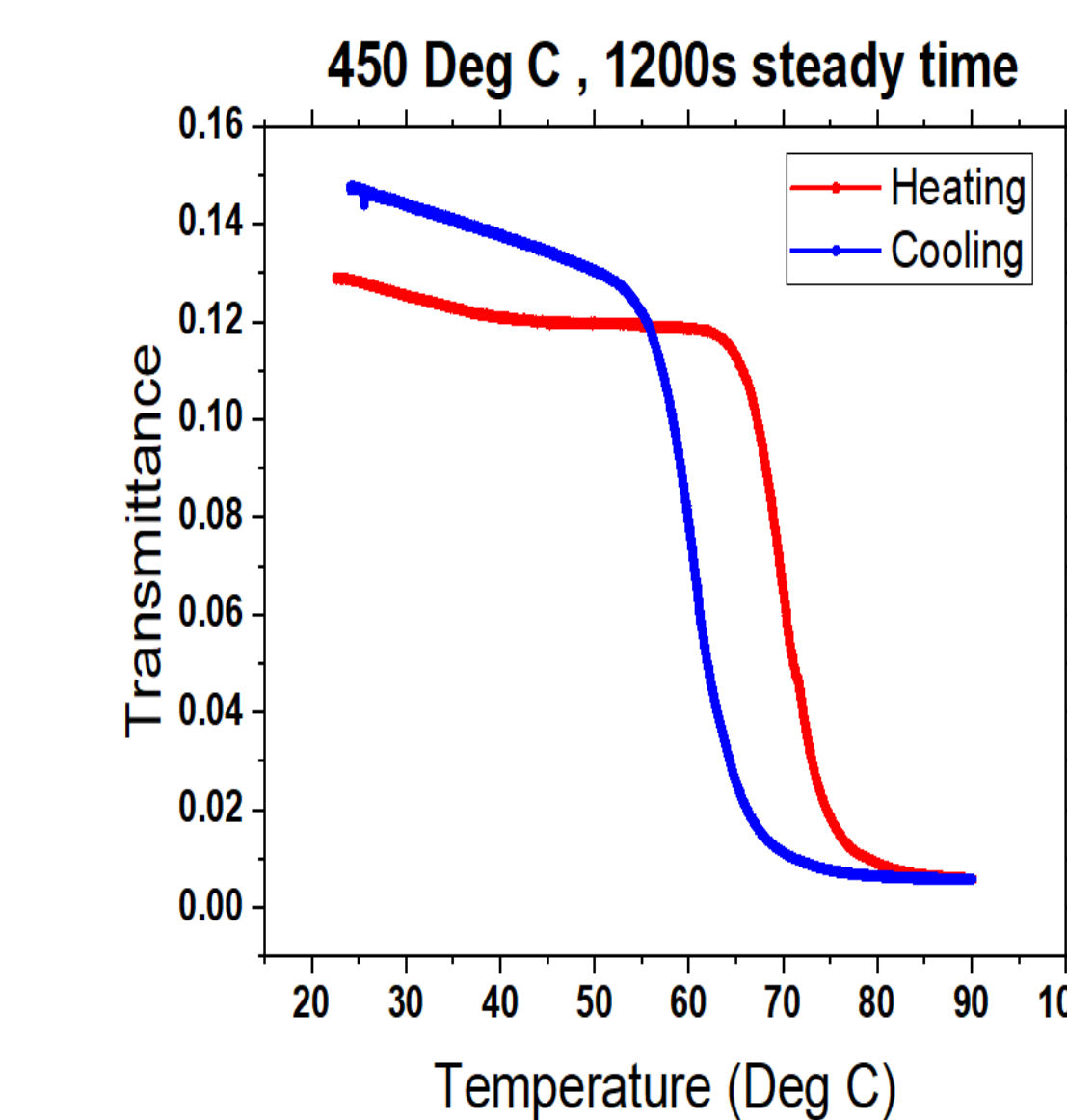
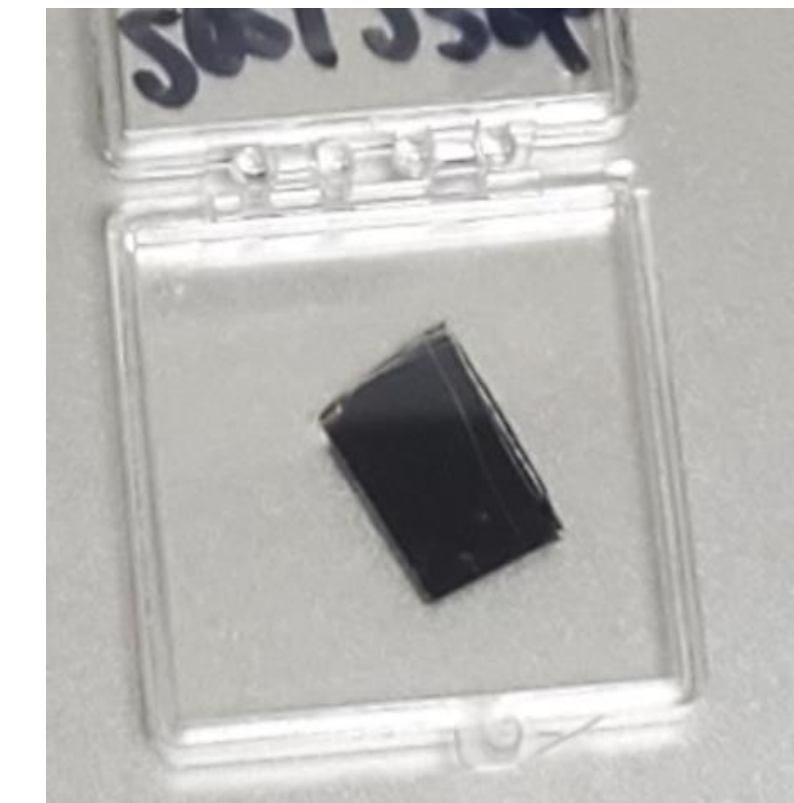
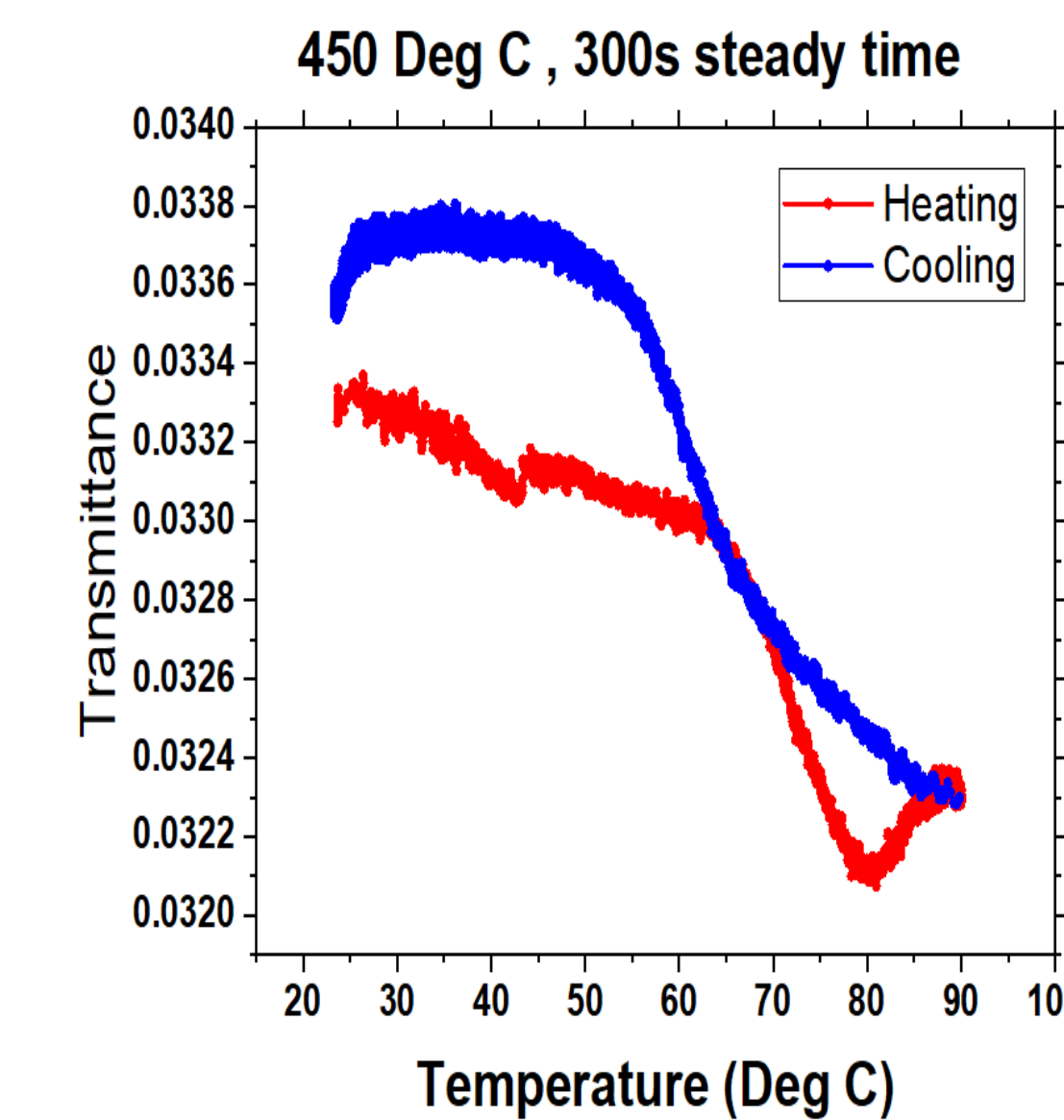


### Measurement Goals

To observe whether the annealed films have successfully been reduced to VO<sub>2</sub>, temperature dependent Transmittance measurements were done



### Results



### Conclusion

With the assistance of external elements like forming gas, RTA has the potential to produce VO<sub>2</sub> films from sputtered VO<sub>x</sub> films

### Acknowledgements

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